



MS ISSUE FEE
PATENT
1691-0170P

B

IN THE U.S. PATENT AND TRADEMARK OFFICE

Applicant: Satoru WAKAMATSU et al. Group: 1773
Application No.: 10/030,657 ✓ Examiner: Hoa T. Le
Filed: January 11, 2002 Conf.: 4641
For: POLYCRYSTALLINE SILICON AND PROCESS AND APPARATUS FOR
PRODUCING THE SAME

LETTER REQUESTING INITIALED PTO 1449 FORM

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

APR 21 2004

Sir:

In reviewing the above-captioned application file upon allowance, the undersigned has noted that acknowledgement was not received for the PTO Form 1449 filed with the Information Disclosure Statement on January 11, 2002.

Accordingly, a copy of each unacknowledged PTO Form 1449 is attached hereto. The Examiner is respectfully requested to return the initialed form to the undersigned as soon as possible.

If necessary, the Commissioner is hereby authorized in this, concurrent, and future replies, to charge payment or credit any overpayment to Deposit Account No. 02-2448 for any additional fees required under 37 C.F.R. §1.16 or under 37 C.F.R. §1.17; particularly, extension of time fees.

Respectfully submitted,

BIRCH, STEWART, KOLASCH & BIRCH, LLP

By 

MARC S. WEINER, #32,181
P.O. Box 747
Falls Church, VA 22040-0747
(703) 205-8000

MSW/jd

INFORMATION DISCLOSURE CITATION
IN AN APPLICATION

GROUP	1	2	3	4	5	6	7	8	9	10	11	12	13	14	15	16	17	18	19	20	21	22	23	24	25	26	27	28	29	30	31	32	33	34	35	36	37	38	39	40	41	42	43	44	45	46	47	48	49	50	51	52	53	54	55	56	57	58	59	60	61	62	63	64	65	66	67	68	69	70	71	72	73	74	75	76	77	78	79	80	81	82	83	84	85	86	87	88	89	90	91	92	93	94	95	96	97	98	99	100
1	1	2	3	4	5	6	7	8	9	10	11	12	13	14	15	16	17	18	19	20	21	22	23	24	25	26	27	28	29	30	31	32	33	34	35	36	37	38	39	40	41	42	43	44	45	46	47	48	49	50	51	52	53	54	55	56	57	58	59	60	61	62	63	64	65	66	67	68	69	70	71	72	73	74	75	76	77	78	79	80	81	82	83	84	85	86	87	88	89	90	91	92	93	94	95	96	97	98	99	100

[illegible][illegible]

EXAMINER: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.